Amendments to the claims:

Cancel claim 1 and add the following new claims.

2. (new) A template matching method for specifying a desired position based on an image obtained by electrons generated by scanning an electron beam on a sample using a template, comprising:

adjusting distance, dimension and/or number of plural parts forming said template, and

specifying said desired position based on said image by using said adjusted template.

3. (new) A template matching method as defined in claim 2, wherein

said template is formed to be plural line pattern or plural hole pattern.

4. (new) A scanning electron microscope comprising an electron gun, a deflector for scanning an electron beam generated from said electron gun, a detector for detecting electrons generated from a sample by irradiating said electron beam on said sample, and a processing unit for forming an image based on an output from said detector and for specifying a desired position based on a previously stored pattern, said scanning electron microscope wherein:

said processing unit adjusts distance, dimension and/or number of plural parts forming said template, and

specifies said desired position based on said image by using said adjusted template.

5. (new) A pattern detecting method for calculating an evaluation value of a pattern based on an image obtained by electrons generated by scanning an electron beam on a sample and for detecting said pattern when said evaluation value of said pattern is not smaller than a predetermined value, comprising:

skipping detection of said pattern when a distance and/or a number of plural parts forming said pattern is smaller than a predetermined threshold value.

6. (new) A pattern detecting method as defined in claim 5, wherein

when said distance and/or said number of plural parts forming said pattern is larger than or equal to said predetermined threshold value, said evaluation value of said pattern is calculated

again, and detection of said pattern is skipped when said evaluation value calculated is smaller than a predetermined threshold value.

7. (new) A pattern detecting method as defined in claim 6, wherein

after the detection of said pattern is skipped, said distance and/or said number of plural parts forming said pattern is judged to determine whether it is larger than or equal to a predetermined threshold value relating to a different pattern.